

Certificate of Analysis (CoA)

Dec. 9, 2025

Product Name: Terbium (Tb) Sputtering Target**Chemical Formula:** Tb**Purity:** 99.9% (3N)**Dimensions:** Ø50.8 mm × 3.18 mm**Bonding:** Bonded to Copper (Cu) Backing Plate, 3 mm thick**Lot Number:** CSJM-251209TB**Quantity:** 1 PCS**Manufactured by:** Thin-Film Materials

Physical Description

- Form: Metallic sputtering target, bonded
- Appearance: Metallic gray, may exhibit a dark surface oxide layer
- Crystal Structure: Hexagonal Close-Packed (HCP)
- Theoretical Density: 8.23 g/cm³
- Fabrication: Vacuum melting/casting, machining, and bonding

Total Impurities (by ICP-OES / GDMS)

Element	Symbol	Max. Content (ppm)
Terbium	Tb	Balance (>99.9%)
Dysprosium	Dy	< 600
Gadolinium	Gd	< 200
Other Rare Earths (Total)	-	< 150
Oxygen	O	< 300
Iron	Fe	< 50
Carbon	C	< 100

Certificate of Analysis (CoA)

Dec. 9, 2025

Handling & Storage

- Terbium is highly reactive. It must be stored under argon or in vacuum-sealed packaging to prevent severe oxidation.
 - Handle in an inert atmosphere glove box whenever possible.
 - Avoid exposure to air and moisture for extended periods.
-

Declaration

We certify that this terbium target meets 3N purity specifications and is suitable for deposition of high-quality thin films in magneto-optical, spintronic, and specialized alloy research applications.

Authorized Signature:

Inspection Certificate by: Nancy Liu

Approver by: Chen Qiang

